

What is claimed is:

1. — A gas distribution assembly comprising:
— a faceplate;
— a blocker plate; and
— an adjustment mechanism coupled to the blocker plate and operable to set a distance between the faceplate and the blocker plate.
2. — The gas distribution assembly of claim 1, wherein the blocker plate comprises a plurality of members.
3. — The gas distribution assembly of claim 2, wherein the plurality of members comprises concentrically arranged bodies about a central axis of the blocker plate.
4. — The gas distribution assembly of claim 2, wherein a distance between each member of the plurality of members is individually adjustable relative to the other members.
5. — The gas distribution assembly of claim 1, wherein the adjustment mechanism comprises an actuator.
6. — The gas distribution assembly of claim 1, wherein the adjustment mechanism comprises spacers.
7. — The gas distribution assembly of claim 1, further comprising a sensor disposed adjacent to the blocker plate.
8. — The gas distribution assembly of claim 1, further comprising an extension coupled to the blocker plate and the adjustment mechanism, wherein a gas flow path is defined within the extension.
9. — A processing chamber comprising:
— a chamber body; —

~~—— a lid coupled to the chamber body, wherein a processing volume is defined within the chamber body and the lid;~~
~~—— a substrate support disposed within the processing volume; and~~
~~—— a gas distribution assembly coupled to the lid, the gas distribution assembly comprising:~~
~~—— a faceplate;~~
~~—— a blocker plate; and~~
~~—— an adjustment mechanism coupled to the blocker plate and operable to set a distance between the faceplate and the blocker plate.~~

~~10. The processing chamber of claim 9, wherein the blocker plate comprises a plurality of members.~~

~~11. The processing chamber of claim 10, wherein the plurality of members comprise concentrically arranged bodies about a central axis of the blocker plate.~~

~~12. The processing chamber of claim 10, wherein a distance between each member of the plurality of members is individually adjustable relative to the other members.~~

13. A method for processing a substrate comprising:
selecting a first processing gas;
positioning a blocker plate relative to a faceplate in response to the selecting the first processing gas, wherein the position of the blocker plate achieves a desired flow distribution of the first processing gas; and
flowing the first processing gas into a processing chamber.

~~14. The method of claim 13, further comprising:~~
~~—— selecting a second processing gas;~~
~~—— positioning the blocker plate relative to the faceplate in response to the selecting the second processing gas, wherein the position of the blocker plate achieves a desired flow distribution of the second processing gas; and~~
~~—— flowing the second processing gas into the processing chamber.~~

15. ~~The method of claim 13,~~

wherein a controller and an actuator are configured to position the blocker plate relative to the faceplate.